# Switching Performance of Mobased pMTJ and DS-MTJ



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### **Outline**

#### Introduction

MRAM

Micromagnetic Model

MTJ and DS-MTJ

Methodology

Mo-based MTJ

Mo-based DS-MTJ

Switching Performance

Conclusion



#### **MRAM**





#### **MRAM**

Magnetic tunnel junction (MTJ):

- Reference layer (RL)
- Tunnel barrier (TB)
- Free layer (FL)
- Reading: tunnel magnetoresistance
- Writing: external field, spin-polarized current
- Non-volatile



- Fast (~ns)
- High endurance (>10<sup>12</sup>)
- Long retention
- CMOS compatible





Parallel





#### Spin-Orbit Torque (SOT) MRAM:

- Faster (< ns)
- Higher endurance
- Bigger foot print (3 terminal)
- Potential SRAM replacement
- Q. Shao et al., IEEE Trans. Magn. 57, 7 (2021)

https://www.everspin.com/spin-transfer-torque-ddr-products

https://www.eeweb.com/mram-technologies-from-space-applications-to-unified-cache-memory/ (2021)

# read/write





Antiparallel

# **Micromagnetic Model**

• Landau–Lifshitz–Gilbert (LLG) equation:

$$\frac{\partial \mathbf{m}}{\partial t} = -\gamma \mu_0 \mathbf{m} \times \mathbf{H}_{eff} + \alpha \mathbf{m} \times \frac{\partial \mathbf{m}}{\partial t} + \frac{1}{M_S} \mathbf{T}_S$$

 $\mathbf{H_{eff}} = \mathbf{H_{aniso}} + \mathbf{H_d} + \mathbf{H_{exch}} + \mathbf{H_{bDMI}} + \mathbf{H_{ext}}$ 

Coupled spin-charge drift-diffusion equations:

$$\begin{aligned} \frac{\partial \mathbf{S}}{\partial t} &= 0 = -\nabla \cdot \overline{\mathbf{J}_{\mathbf{S}}} - D_e \left( \frac{\mathbf{S}}{\lambda_{sf}^2} + \frac{\mathbf{S} \times \mathbf{m}}{\lambda_J^2} + \frac{\mathbf{m} \times (\mathbf{S} \times \mathbf{m})}{\lambda_{\varphi}^2} \right) \\ \overline{\mathbf{J}_{\mathbf{S}}} &= -\frac{\mu_B}{e} \beta_{\sigma} \mathbf{m} \otimes \left( \mathbf{J}_{\mathbf{C}} - \beta_D D_e \frac{e}{\mu_B} \left[ (\nabla \mathbf{S})^{\mathbf{T}} \mathbf{m} \right] \right) - D_e \nabla \mathbf{S} - \theta_{SHA} \frac{\mu_B}{e} \varepsilon \mathbf{J}_{\mathbf{C}} \\ \mathbf{J}_{\mathbf{C}} &= -\sigma \nabla V \end{aligned}$$



- TB treated as poor conductor dependent on relative magnetization orientation of FL & RL
- External boundaries:  $Jc \cdot n = 0$ ,  $Js \cdot n = 0$ .
- Solve for a steady state

C. Abert et al., Scientific Reports 5, 14855 (2015) S. Lepadatu, Scientific Reports 7, 12937 (2017) S. Fiorentini et al., Micromachines 14, 898 (2023) G. Hrkac et al., Adv. Comput. Math. 45, 3 (2019)



# **Tunnel Barrier**

Charge current

- Tunnel barrier modeled as poor conductor
- Conductance depends on angle between  $\mathbf{m_{RL}}$  and  $\mathbf{m_{FL}}$  (TMR)

$$J_C^{TB} = J_0(V) (1 + P_{RL} P_{FL} \cos \theta)$$



Spin Current

- Boundary condition at TB interfaces

$$\overline{J}_{s} = -\frac{\mu_{B}}{e} \frac{J_{C} \cdot n}{1 + P_{RL} P_{FL} \cos \theta} \left( \alpha_{RL} P_{RL} m_{RL} + \alpha_{FL} P_{FL} m_{FL} + \frac{1}{2} \left( P_{RL} P_{RL}^{\eta} - P_{FL} P_{FL}^{\eta} \right) m_{RL} \right)$$

- Magnetization in free layer during switching



- Magnetization in free layer during switching



### **Increasing STT-Switching Performance**

Mo-based perpendicular MTJ

- Up to sub-ns switching performance
- strong PMA and thermal tolerance

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Sub-ns Switching and Cryogenic-Temperature Performance of Mo-Based Perpendicular Magnetic Tunnel Junctions

1215

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Double spin-torque magnetic tunnel junction (DS-MTJ) Double spin-torque magnetic tunnel junction devices

FI

R

- Second ferromagnetic reference layer (RL) on top
- Separated from free layer (FL) by non-magnetic spacer (NMS)
- 2 RLs with antiparallel magnetization
- Additional torque coming from 2<sup>nd</sup> RL acting in FL ("double" spin-torque)

D. Lyu at al., IEEE Electron Device Letters, 43, 8, 1215-1218, (2022) G. Hu et al., 2022 International Electron Devices Meeting (IEDM), pp. 10.2.1-10.2.4, (2022)

for last-level cache applications

G. Hu, C. Safranski, J. Z. Sun, P. Hashemi, S. L. Brown, J. Bruley, L. Buzi, C. P. D'Emic, E. Galligan, M. G. Gottwald, O. Gunawan, J. Lee, S. Karimeddiny, P. L. Trouilloud, and D. C. Worledge IBM-Samsung MRAM Alliance, IBM TJ Watson Research Center, Yorktown Heights, New York, email: <u>hug@us.ibm.com</u>



## **Switching Performance of MTJ and DS-MTJ**



## **DS-MTJ – Influence of non-magnetic spacer**

- Switching perfomance strongly dependent on NMS-material
- Spin-flip length λ<sub>sF</sub> determines additional torque in FL
- $\lambda_{\text{SF}}$  governs decay of longitudinal components of the spin current

Tantalum (Ta):  $\lambda_{SF} = 1.9$  nm, Ruthenium (Ru):  $\lambda_{SF} = 4$  nm





# Conclusion

- Double Spin-Torque Magnetic Tunnel Junctions (DS-MTJ) show 2x faster switching than regular MTJ
- Application of the DS-MTJ structure to promising Mo-based MTJ
- DS-MTJ structure shows increased switching performance (Subns switching)
- strongly dependent on material of non-magnetic spacer
- Spin-flip length  $\lambda_{sF}$  influences additional spin-torque in free layer

Switching Performance of Mo-base pMTJ and DS-MTJ Pruckner Bernhard, pruckner@iue.tuwien.ac.at